

	Hit s	Search Text	DBs
33	81	(projection near9 (optical or \$5lithograph\$4) near9 (system or apparatus)) and ((radiation or light or optical or laser or project\$4 or \$4lithograph\$6) same (source or system or apparatus)) and ((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3)) and pattern\$4 and ((plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV)) and ((pattern\$6 near5 device) or mask\$4 or reticle or photo\$4mask) and (gas\$3 same (plasma or ion\$3beam or beam or laser or ion\$4assist\$5) same (((nitrogen or nitrous or nitric) near16 (oxide or dioxide)) or "NO.sub.2")))	US - PGPUB; USPAT; EPO; JPO; DERWENT; <u>IBM_TDB</u>

	Hit s	Search Text	DBs
34	21	(projection near9 (optical or \$5lithograph\$4) near9 (system or apparatus)) and ((radiation or light or optical or laser or project\$4 or \$4lithograph\$6) same (source or system or apparatus)) and ((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3)) and pattern\$4 and ((plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV)) and (((pattern\$6 near5 device) or mask\$4 or reticle or photo\$4mask) same (support or driv\$3 or stage or hold\$3)) and (gas\$3 same (plasma or ion\$3beam or beam or laser or ion\$4assist\$5 or (high near4 energy)) same (((nitrogen or nitrous or nitric) near16 (oxide or dioxide or oxygen)) or "NO.sub.2") same ((clean\$4 or remov\$4 or strip\$4) near19 (contaminant\$2 or residu\$3 or oxide)))	US_PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB